

- (1) DE 102 44 040 C1
- (2) ABC Glas, Deutscher Verlag für Grundstoffindustrie [*German Publisher for Basic Industry*], Leipzig, 2nd Edition 1991; page 81 through 84

Claim 1 relates to a method for treating refractory material, the surface of which is treated by laser radiation.

Reference is made in this regard to (1). See (1), particularly Claims 1 and 6 in combination with column 4, lines 8 through 9 ("silica glass particles"). With regard for the term "refractory material", refer to (2), particularly picture 3 on page 83 ("silica").

Claim 1 is therefore not allowable. Claims 2 through 9 fall along with Claim 1, due to lack of independently patentable measures. Regarding Claim 4, it should also be pointed out that it is not clear what is meant by the term "effective" exposure time.

Claim 10 relates to refractory material, characterized by a surface treated by laser radiation.

The statement made with regard for Claim 1, above, also applies in this case.

Claim 10 is not allowable. Claims 11 through 13 fall along with it, due to lack of independently patentable features. Claim 14 falls as well, which is directed to the application, and refers back to these claims.

Regarding Claim 14, refer also to sentence [0002] in (1).

Claim 15 relates to a device, and Claim 16 relates to a method for manufacturing and/or processing glass melts with refractory material in contact with glass melts; the refractory material has a surface treated by laser radiation.

With regard for concurrently possible claims categories, refer to the table in Schulte PatG [*Patent Law*], Version 6, § 34, after lit 217. The application is not uniform.

From a substantive perspective, reference is made to (1) with regard for Claim 15 and 16. The statements made regarding Claim 1, above, also apply in this case.

Claims 15 and 16 are not allowable.

Given these circumstances, a patent is not likely to be granted; instead, the application is most likely to be rejected.

Examiner for Class C 03 B

Dr. Pötschke

Attachment: Copies of 2 references